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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/891,885	06/26/2001	Mark T. Ramsbey	F0279	2423
23623	7590	04/08/2004	EXAMINER	
AMIN & TUROCY, LLP 1900 EAST 9TH STREET, NATIONAL CITY CENTER 24TH FLOOR, CLEVELAND, OH 44114			MAGEE, THOMAS J	
			ART UNIT	PAPER NUMBER
			2811	

DATE MAILED: 04/08/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

Office Action Summary	Application No. 09/891,885	Applicant(s) RAMSBEY ET AL.	
	Examiner Thomas J. Magee	Art Unit 2811	

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --
Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

- 1) ☒ Responsive to communication(s) filed on 08 January 2004.
 2a) ☒ This action is **FINAL**. 2b) ☐ This action is non-final.
 3) ☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

- 4) ☒ Claim(s) 9, 11-13 and 16-18 is/are pending in the application.
 4a) Of the above claim(s) _____ is/are withdrawn from consideration.
 5) ☐ Claim(s) _____ is/are allowed.
 6) ☒ Claim(s) 9, 11-13, and 16-18 is/are rejected.
 7) ☐ Claim(s) _____ is/are objected to.
 8) ☐ Claim(s) _____ are subject to restriction and/or election requirement.

Application Papers

- 9) ☐ The specification is objected to by the Examiner.
 10) ☐ The drawing(s) filed on _____ is/are: a) ☐ accepted or b) ☐ objected to by the Examiner.
 Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
 Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
 11) ☐ The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

Priority under 35 U.S.C. § 119

- 12) ☐ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
 a) ☐ All b) ☐ Some * c) ☐ None of:
 1. ☐ Certified copies of the priority documents have been received.
 2. ☐ Certified copies of the priority documents have been received in Application No. _____.
 3. ☐ Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).
 * See the attached detailed Office action for a list of the certified copies not received.

Attachment(s)

- | | |
|--|---|
| 1) <input checked="" type="checkbox"/> Notice of References Cited (PTO-892) | 4) <input type="checkbox"/> Interview Summary (PTO-413)
Paper No(s)/Mail Date. _____ |
| 2) <input type="checkbox"/> Notice of Draftsperson's Patent Drawing Review (PTO-948) | 5) <input type="checkbox"/> Notice of Informal Patent Application (PTO-152) |
| 3) <input type="checkbox"/> Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)
Paper No(s)/Mail Date _____ | 6) <input type="checkbox"/> Other: _____ |

DETAILED ACTION

Claim Cancellations

1. Applicant's cancellation of claims 10 and 15 in Letter of January 8, 2004 is acknowledged.

Claim Objections

2. Claim 11 is objected to under 37 CFR 1.75(c), as being of improper dependent form for failing to further limit the subject matter of a previous claim. Claim 11 contains the phrase, "*the method of Claim 10*," but there is no Claim 10 since it has been cancelled by Applicant. Applicant is required to cancel the claim, or amend the claim in proper dependent form, or rewrite the claim in independent form.

Claim Rejections – 35 U.S.C. 103

3. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office Action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negated by the manner in which the invention was made.

4. Claims 9, 11, and 16 are rejected under 35 U.S.C. 103(a) as being unpatentable over Liang et al. (US 6,355,962 B1) in view of Huang (US 5,378,649) and Fang (US 6,667,511 B1).

5. Regarding Claim 9, Liang et al. disclose a method of forming a flash (non-volatile)

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memory device, wherein a substrate is provided with memory devices (Col. 1, lines 65 – 67), with one or more insulating regions (20) (Figure 1E) for one or more ESD transistors (Col. 1, lines 62 – 64) formed in the periphery region of the flash memory array (left side, Figure 1E) and poly layers (22A,22B, Figure 1E) over the insulating layers. Liang et al. disclose that after patterning to form ESD and other transistors, spacers are formed (Col. 2, lines 55 – 56) (Figure 1E, 32). Further, Liang et al. disclose that heavy (n+) doping is done with the spacers in place to form source/drain regions (34) (Figure 1E) (Col. 3, lines 7 – 9) for the ESD transistors without masking other transistors in the region.

Liang et al. do not disclose distinct core and peripheral regions. However, Fang discloses (Figure 1a) (Col. 1, lines 21 – 27) that typical non-volatile memory devices comprise one or more high density core regions (11) and a low density peripheral portion on a single substrate. It would have been obvious to one of ordinary skill in the art at the time of the invention to combine Fang with Liang et al. to obtain a properly implemented memory device layout.

Liang et al. do not explicitly disclose that word lines in the core region are spaced apart by 1 μm or less. Huang discloses that the polycrystalline silicon word lines used in a non volatile memory device are spaced at a distance in the range, 0.1 to 0.5 μm , consistent with the value recited in the instant application. It would have been obvious to one of ordinary skill in the art at the time of the invention to combine Liang et al. and Huang to obtain polysilicon word lines at appropriate spacings to reduce crosstalk and coupling.

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6. Regarding Claims 11 and 16, Liang et al. disclose (Col 5, lines 10 – 13) that the source/drain regions are formed by heavy implants of arsenic or phosphorus at an energy of 80 keV to a dose of about $10^{16}/\text{cm}^2$, consistent with the recitation of claims in the instant application.

7. Claims 12 and 13 are rejected under 35 U.S.C. 103(a) as being unpatentable over Liang et al. in view of Huang et al. and Fang as applied to Claims 9, 11, and 16, and further in view of Reisinger (US 6,137,718).

8. Regarding Claims 12 and 13, Liang et al. do not explicitly disclose that the flash memory array is a SONOS type structure, but this would have been an easy modification. SONOS cells have been present since the late 1960's. Reisinger discloses (Col. 8, lines 5 12) the formation of MOS transistors with multi-layer dielectrics (51,52,53) capped by a polysilicon layer (6) (See Figure 1) to produce a classical SONOS structure for a non-volatile memory cell. Hence, it would have been obvious to one of ordinary skill in the art at the time of the invention to add Reisinger to Liang et al. to obtain a SONOS structure with improved dielectric properties and increased storage density in the memory circuit (Reisinger, Abstract).

9. Regarding Claims 17 and 18, as discussed above for Claim 9, Liang et al. disclose a method of forming a flash (non-volatile) semiconductor memory device, wherein a substrate is provided with memory devices in a core region with one or more insulating regions (20)

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(Figure 1E). Liang et al. further disclose (Col. 4, lines 10 – 14) the formation of lightly doped source /drain regions using implants of about 10^{14} ions/cm² at an energy of about 80 keV. Liang et al. disclose that after patterning to form ESD and other transistors, spacers are formed (Col. 2, lines 55 – 56) (Figure 1E, 32) from deposited dielectric material. Further, Liang et al. disclose that heavy (n+) doping is done using arsenic or phosphorus at an energy of 80 keV to a dose of about 10^{16} /cm² (Col. 5, lines 10 – 13) with the spacers in place to form source/drain regions (34) (Figure 1E) (Col. 3, lines 7 – 9) for the ESD transistors without masking other transistors in the region.

Response to Arguments

10. Applicant's arguments with respect to claims have been considered but are moot in view of the new ground(s) of rejection.

Conclusions

11. Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

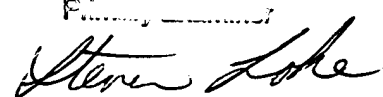
A shortened statutory period for reply to this final action is set to expire **THREE MONTHS** from the mailing date of this action. In the event a first reply is filed within **TWO MONTHS** of the mailing date of this final action and the advisory action is not

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mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

Any inquiry concerning this communication or earlier communications from the Examiner should be directed to **Thomas Magee**, whose telephone number is **(571) 272 1658**. The Examiner can normally be reached on Monday through Friday from 8:30AM to 5:00PM (EST). If attempts to reach the Examiner by telephone are unsuccessful, the examiner's supervisor, **Eddie Lee**, can be reached on **(571) 272-1732**. The fax number for the organization where this application or proceeding is assigned is **(703) 872-9306**.

Thomas Magee
March 26, 2004


Steven Lake